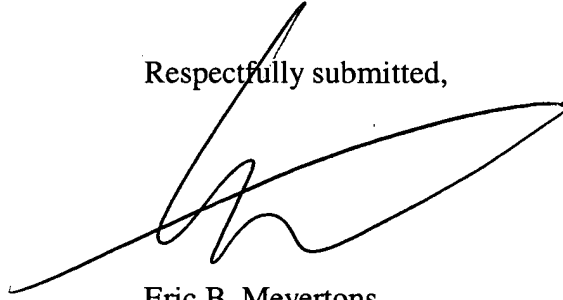


**PATENT  
5310-03000**

Inventors: Halimaoui et al.  
Appl. Ser. No.: 09/744,877  
Atty. Dkt. No.: 5310-03000

It is believed that no fees are associated with filing of this Information Disclosure Statement. Should any fees be required, the Commissioner is authorized to charge said fees to Meyertons, Hood, Kivlin, Kowert & Goetzel, P.C. Deposit Account No. 50-1505/5310-03000/EBM.

Respectfully submitted,

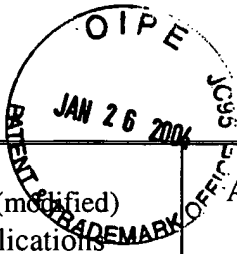
A handwritten signature in black ink, appearing to be 'Eric B. Meyertons', written over the words 'Respectfully submitted,'.

Eric B. Meyertons  
Reg. No. 34,876

Attorney for Applicant

MEYERTONS, HOOD, KIVLIN, KOWERT & GOETZEL, P.C.  
P.O. BOX 398  
AUSTIN, TEXAS 78767-0398  
(512) 853-8800 (voice)  
(512) 853-8801 (facsimile)

Date: 1/21/04

**Form PTO-1449** (modified)

List of Patents and Publications  
For Applicant's Information  
Disclosure Statement  
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ATTY. DOCKET NO: 5310-03000

APPLICANT: Halimaoui et al.

FILING DATE: January 29, 2001

SERIAL NO: 09/744,877

CONFIRMATION NO.: 8711

ART UNIT: 2822

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	A1	5,021,354	6/1991	Pfiester			
	A2	5,106,768	8/1998	Kuo			

**FOREIGN PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION. YES/NO
	A3	61016530	1/1986	JP			Abstract
	A4	97 41593	11/1997	WO			

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

	A5	Soleimani et al.; "Formation of Ultrathin Nitrided SiO <sub>2</sub> Oxides by Direct Nitrogen Implantation into Silicon"; <i>J. Electrochem. Soc.</i> , 1995, 42(10).

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.